

Form PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. SCKET NO.
M122-1098PRIORITY SERIAL NO.
08/696,243LIST OF ART CITED BY APPLICANT
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Klaus F. SchuegrafPRIORITY FILING DATE
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2813

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
EK	AA	5,763,018	6/1998	Sato	438	790	
EK	AB	5,710,079	1/1998	Sukharev	438	778	
	AC	5,238,671	8/1993	Matson et al.	423	397	
	AD	5,610,105	3/1997	Vines et al.	437	238	
	AE	5,472,913	12/1995	Havemann et al.	437	238	
	AF	5,470,800	11/1995	Muroyama	437	238	
	AG	5,462,899	10/1995	Ikeda	437	238	
	AH	5,580,822	12/1992	Hayakawa et al.	437	187	
	AI	5,420,075	5/1995	Homma et al.	437	195	
EK	AJ	5,360,646	11/1994	Morita	427	574	

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL	6349747	12/1994	Japan				
	AM							
	AN							
	AO							
	AP							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

EK	AR	IslamRaja, et al., "Two Precursor Model For Low-Pressure Chemical Vapor Deposition Of Silicon Dioxide From Tetraethylorthosilicate", J. Vac. Sci. Technol. B, Vol. 11, No. 3, May/Jun 1993, pp. 720-726.
EK	AS	Crowell, John E. et al., "The Chemical Vapor Deposition Of SiO ₂ From TEOS", Journal of Electron Spectroscopy And Related Phenomena, 54/55 (1990) pp. 1097-1104.
EK	AT	Hauptfear, E.A. et al., "Kinetics of SiO ₂ Deposition From Tetraethylorthosilicate", Electrochem. Soc. Vol. 141, No. 7, July 1994, pp. 1943-1950.

EXAMINER

EK/Kelvin

DATE CONSIDERED

6/14/20

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1098	PRIORITY SERIAL NO. 08/696,243
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Klaus F. Schuegraf	
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U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
CK	AA	5,182,221	1/1993	Sato	437	67	
	AB						
	AC						
	AD						
	AE						
	AF						
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	AI						
	AJ						

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
AL							
AM							
AN							
AO							
AP							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
CK	AR		Wolf, Stanley, "Silicon Processing for the VLSI Era", Vol. 1, pp. 166-171
CK	AS		"Hawley's Condensed Chemical Dictionary", 12th Ed., 1993, pg. 500
	AT		

EXAMINER <i>Carl Koster</i>	DATE CONSIDERED <i>6/14/00</i>
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